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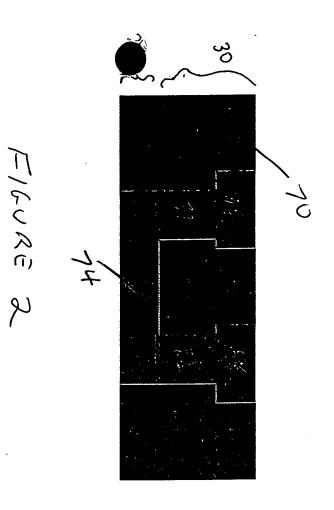
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2. Cu3 CMP

3. Metals and MOM oxide deposition



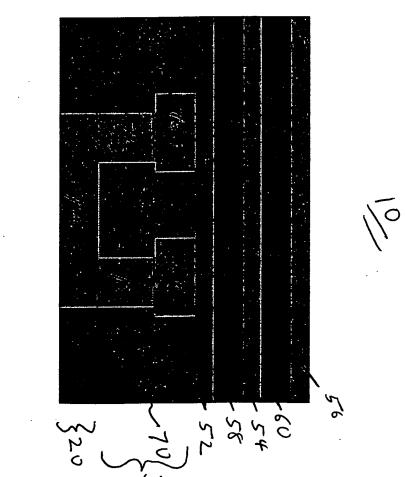


Fig. 2&3

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FIGURE 3

4. Notch etch for contact to metal B

5. Metal and oxide etch

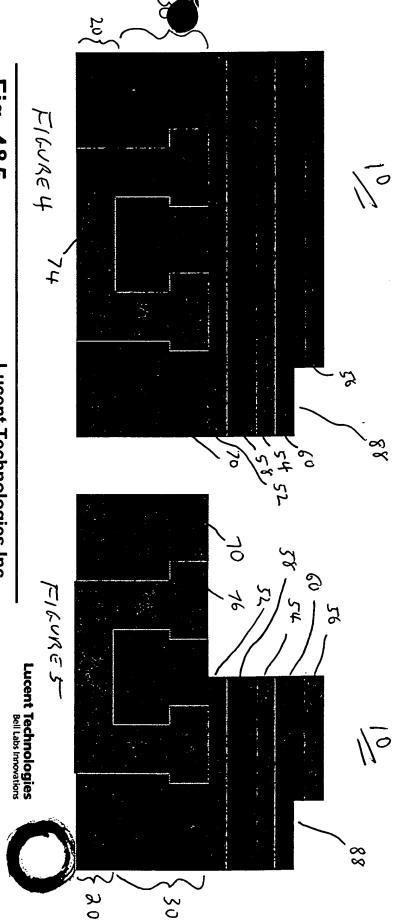


Fig. 4&5

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6. SiN4 and dielectric 4 deposition

7. Dielectric 4 CMP

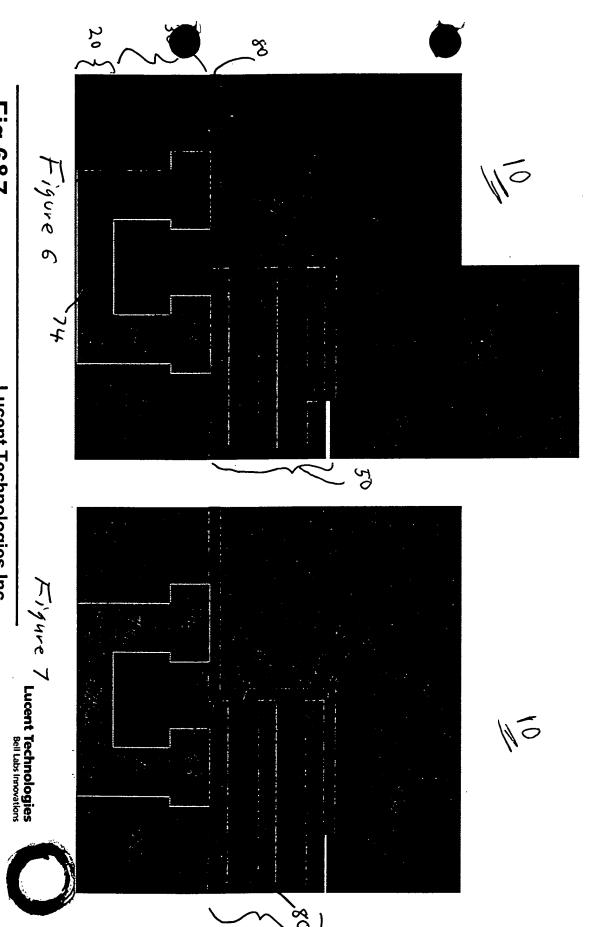
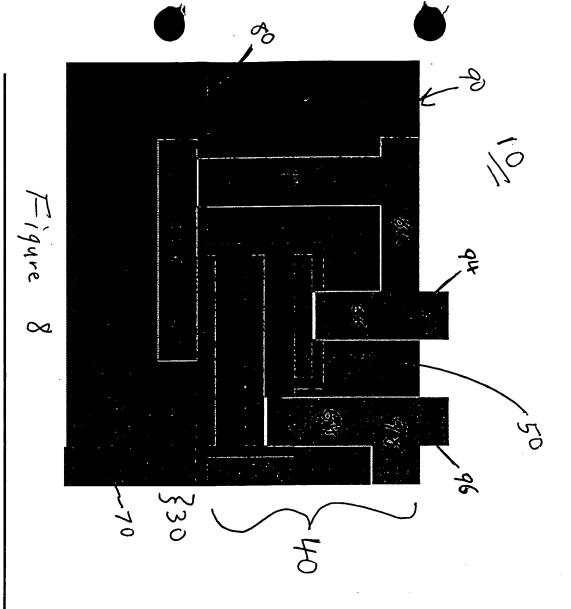


Fig.6&7

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8. Another version of doublemom

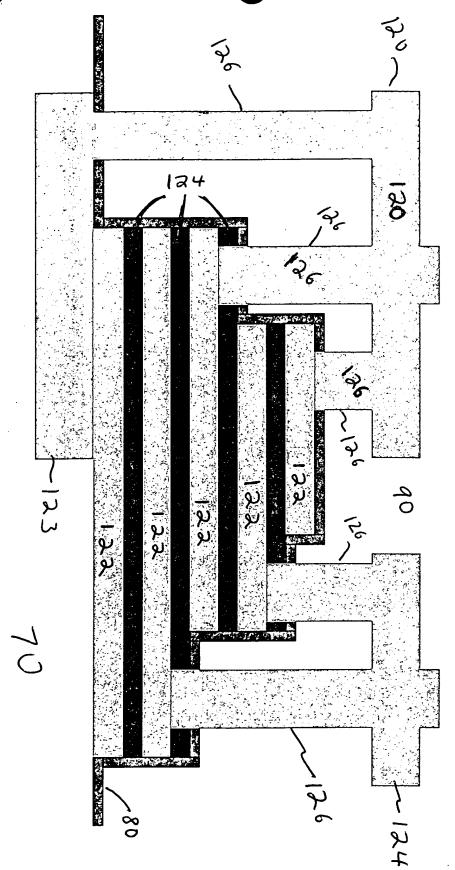


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FILURE 9

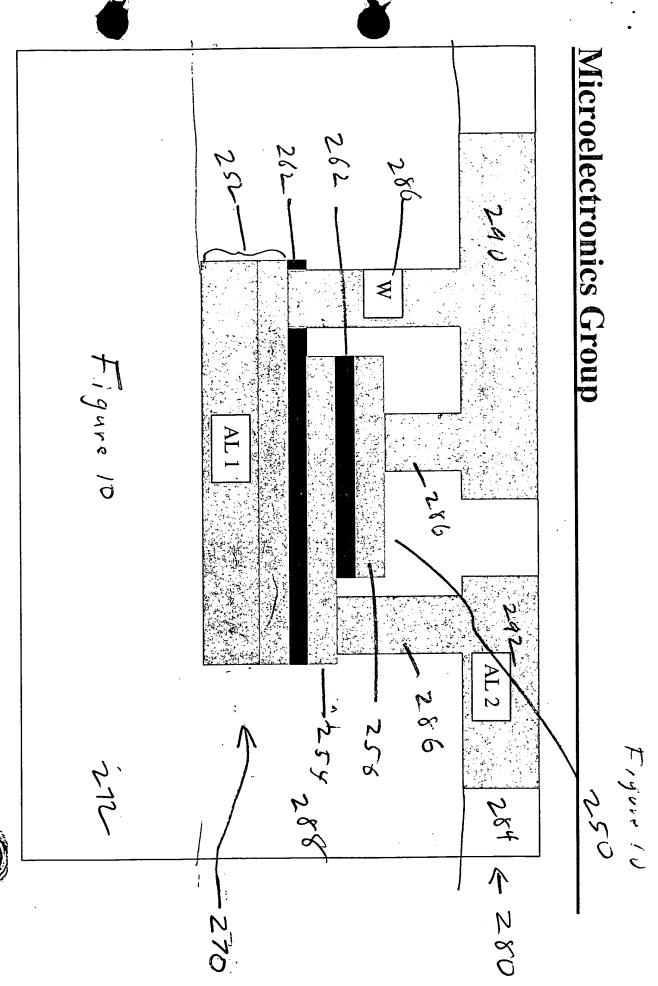
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Fig. 9

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